

# HAPSPIDE

## WP3 Simulation

18/11/2021

## WP3 TASKs (description)

- 3.1 Modeling development/validation.
- 3.2 Geant4 simulations.
- 3.3 TCAD simulations: DC, (AC), transient analysis (CCE).
- 3.3 Optimization of a-Si:H devices: layout/geometries, operating conditions.
- 3.4 Radiation tolerance analysis.

## WP3 Milestones

- 3.1 TCAD modeling of a-Si:H – **M6**.
- 3.2 Combined Geant4 + TCAD simulation environment set-up – **M12**.
- 3.3 Comparison between simulations and measurements – **M18**.

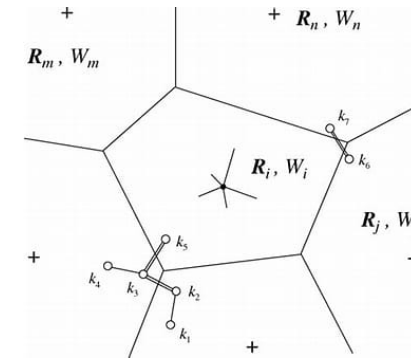
## WP3 Deliverables / Timescale

- 3.1 a-Si:H TCAD material model with embedded physical models (e.g. carrier mobility) - **M6**.
- 3.2 Report on layout/geometry of dosimetric flux sensor - **M12**.
- 3.3 Report on layout/geometry of single particle sensor - **M18**.
- 3.4 Radiation damage model – **M36**

- **WP3 Simulations – A twofold framework**
  - **Dosimetric** measurements and **single particle** detection.
  - **Monte-Carlo** approach (**GEANT4**) , aiming at accurate description of the material/particle interaction accounting for secondary emission effects, linear energy transfer value variations, effect of packaging materials on tissue equivalency for charge particles and photons, simulation of the expected micro-dosimetric spectra for different sensitive volume geometries and charge particle beam energy (-> input for TCAD simulations...).
  - **Technology CAD (TCAD)** approach (**Sentaurus Synopsys TCAD**), aiming at accurate description of the charge transport within a-Si:H material and device electrical response (DC, transient simulations).
  - The **effect of the read-out mode** (e.g. single-event vs. continuous current measurement) can be self-consistently accounted for within TCAD simulation, exploiting the mixed device-circuit simulation embedded option.

- Innovation: a-Si:H not included in TCAD material library

- Semiconductor ( $\sim$  uniform domain macro properties) – band gap engineering (**defects parametrization**).
- Atomistic scale ? (grain boundary effect, Voronoi domains).



- Charge Transport: mobility models

- Poor modeling with existing models (e.g. Poole-Frenkel).
- The (drift) mobility can't be straightforwardly inferred from the current density approximation

- $$J = AT^2 \left[ \exp \left( bT \sqrt{\frac{V}{d}} \right) - 1 \right] \Leftrightarrow J = q\mu nE.$$

- Dependence of  $\mu$  upon doping, electric field, ...

- Study of LIFETIMES vs. MOBILITY models
  - Interplay in current densities calculations.
- Introduction of innovative materials (from TCAD perspective)
  - Transparent Contact Oxides (TCO) -> transport modeling within oxides.
  - Electrons/Holes **selective Contacts** -> selective mobility for e, h.

- Simulations vs. measurements @mobility/lifetimes models
  - Current activities/starting point.

